

## Direct Observation of Intraionic and Interconfigurational Excitations in an Intermediate-Valence Compound by Raman Spectroscopy

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Intraionic spin-orbit-split multiplet levels have been observed by electronic Raman scattering in the intermediate-valence compound  $\text{EuPd}_2\text{Si}_2$ . From the temperature dependence of the Raman peak positions and widths the interconfigurational excitation energy  $E_x$  and an upper limit of the interconfigurational mixing width  $T_f$ , respectively, have been obtained. This is the first spectroscopic support for the underlying assumptions of the ionic interconfigurational fluctuation model that has been proposed to describe intermediate valence.

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In rare-earth intermediate-valence (IV) systems the strongly correlated nature of the localized  $4f$  states makes the theoretical treatment of their interaction with conduction electrons a rather difficult problem.<sup>1</sup> In the interconfigurational fluctuation (ICF) model an approach based on a purely ionic  $4f$  configuration has been chosen.<sup>2</sup> In this model the interaction between two  $4f$  configurations ( $4f^n \leftrightarrow 4f^{n-1} + e^-$ ) is parameterized by the interconfigurational excitation energy ( $E_x$ ) and by the interconfigurational mixing width or fluctuation temperature ( $T_f$ ) of the multiplet levels. The ionic model has been used to extract the temperature dependence of  $E_x$  and  $T_f$  from magnetic-susceptibility and Mössbauer data<sup>3,4</sup> and to provide a semiquantitative understanding thereof in the framework of phenomenological thermodynamics.<sup>3,5</sup> However, in our opinion there has been so far no direct spectroscopic proof for the validity of the basic assumptions of the ionic model. The latter concern the persistence of individual ionic  $4f$  multiplet levels characterized by their total angular momentum  $J$  and the temperature-induced shift of the two rigid  $4f^n$  and  $4f^{n-1}$  multiplets with respect to each other, described by  $E_x(T)$ .

In this paper we report the spectroscopic observation of ionic spin-orbit-split  $J$ -multiplet levels in the IV compound  $\text{EuPd}_2\text{Si}_2$  by means of electronic Raman scattering. The temperature dependence of  $E_x$  and of the upper limit of  $T_f$  is directly revealed in the Raman spectra. Our results support the salient features of the ionic ICF model<sup>2</sup> and are in reasonably good agreement with the  $E_x$  and  $T_f$  deduced from the Mössbauer and magnetic-susceptibility data.<sup>4</sup>

Raman-scattering measurements were carried out on

freshly fractured polycrystals of  $\text{EuPd}_2\text{Si}_2$  between 300 and 4.2 K. In Fig. 1 the Raman spectra of  $\text{EuPd}_2\text{Si}_2$  obtained with 5309-Å laser excitation are shown for selected temperatures. On the top of the figure the  $J$ -multiplet levels observed by electronic Raman scattering in  $\text{SmSe}$ <sup>6</sup> are shown. The maxima observed in  $\text{EuPd}_2\text{Si}_2$  are close in energy to the  $J$ -multiplet levels of  $\text{SmSe}$ . This is to be expected, since the  $J$  levels of  $\text{Eu}^{3+}$  should be the same as those of the  $\text{Sm}^{2+}4f^6(^7F_J)$  configuration. The  $J$ -multiplet levels of IV  $\text{EuPd}_2\text{Si}_2$  at 300 K are quite broad compared to the  $J$  levels of divalent  $\text{SmSe}$ . Upon cooling to 200 K, the  $J$  levels of  $\text{EuPd}_2\text{Si}_2$  undergo an asymmetric broadening and this is most clearly seen for the  $J=3$  and  $J=4$  levels. This broadening develops into a well-pronounced splitting at 145 K, which is rather well seen in the case of  $J=2, 3$ , and 4 levels. At 77 K the splitting of individual  $J$  levels has disappeared, yielding a single broadened peak for each one of the  $J$  levels. The spectrum at 4.2 K reveals well defined  $J$ -multiplet levels similar to the spectrum at 300 K. The reproducibility of the spectral features in Fig. 1 is slightly affected presumably by local strains giving rise to frequency shifts of the levels up to 3%. The overall background in Fig. 1 arises mainly from sample imperfections causing luminescence emission. So far we have not been able to observe any Raman-active phonons in  $\text{EuPd}_2\text{Si}_2$ , or in the reference compound  $\text{LaPd}_2\text{Si}_2$ , both of which crystallize in the tetragonal  $\text{ThCr}_2\text{Si}_2$  structure.

In Fig. 2 we show a schematic energy-level diagram explaining the electronic Raman scattering from the  $J$ -multiplet levels in an IV Eu compound. The  $(\text{Eu}^{2+})4f^7$  and  $(\text{Eu}^{3+})4f^6 + e^-$  configurations are

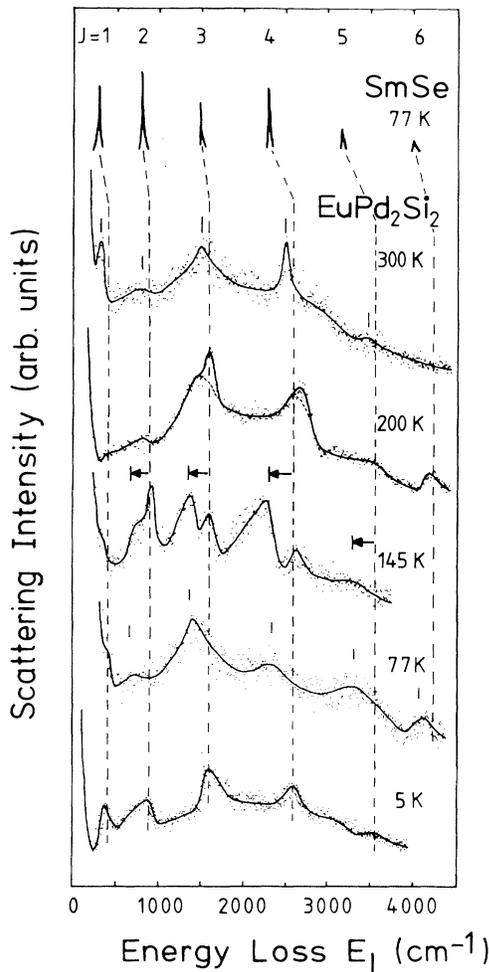


FIG. 1. Raman spectra of  $\text{EuPd}_2\text{Si}_2$  at different temperatures under 5309-Å laser excitation. Vertical dashed guide lines mark the intraconfigurational excitations ( $E_{L,\text{intra}}$ ) of the  $4f^7 4f^6(^7F_J)$  configuration; solid lines through spectra are guide lines to the eye. Top of the figure: electronic Raman scattering due to the  $\text{Sm}^{2+} 4f^6(^7F_J)$  configuration of  $\text{SmSe}$  (Ref. 6).

nearly degenerate and separated by  $E_x$ . When  $E_x \neq 0$  two sets of inelastic energy losses  $E_{L,\text{intra}}$  and  $E_{L,\text{inter}} = E_{L,\text{intra}} - E_x$  are possible for the  $J$ -multiplet levels of the  $4f^6$  configuration. These are the *intraconfigurational* excitations ( $E_{L,\text{intra}}$ ) of the  $J = 1, \dots, 6$  levels with respect to the  $(4f^6) J = 0$  initial state and the *interconfigurational* excitations ( $E_{L,\text{inter}}$ ) with respect to the  $(4f^7) J = \frac{7}{2}$  initial state. The interconfigurational excitation energy  $E_x$  itself should also show up with respect to the  $J = 0$  initial state. The inelastic scattering intensity of the interconfigurational excitations ( $4f^7 \rightarrow 4f^6 + e^-$ ) is obtained in second-order perturbation theory and should be stronger than for the magnetic-dipole allowed intraconfigurational excitations ( $J = 0 \rightarrow J \neq 0$ ). The latter contribute to

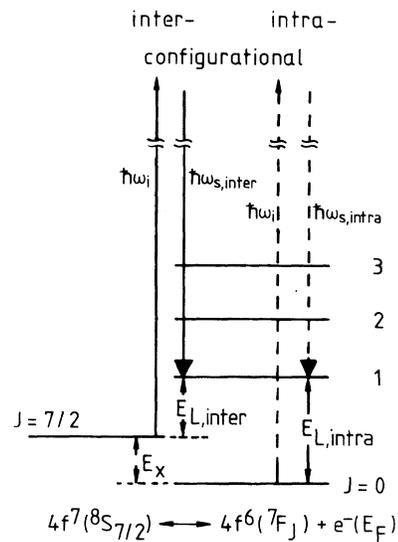


FIG. 2. Schematic representation of the electronic Raman scattering process in an intermediate-valence Eu compound showing an interconfigurational excitation energy  $E_x \neq 0$ . Indicated are the *intraconfigurational* energy losses ( $E_{L,\text{intra}}$ ) and the *interconfigurational* energy losses ( $E_{L,\text{inter}} = E_{L,\text{intra}} - E_x$ ) of the incident photon  $\hbar\omega_i$  with respect to the  $J = 0$  and  $J = \frac{7}{2}$  initial state, respectively.

the scattering cross section in third-order perturbation theory involving spin-orbit coupling.

We now turn to the interconfigurational excitation energy  $E_x$  and its temperature dependence which is given by the *common, rigid shift* of all interconfigurational excitations ( $E_{L,\text{inter}}$ ) with respect to the intraconfigurational  $J$ -multiplet excitations ( $E_{L,\text{intra}}$ ). The latter have been indicated in Fig. 1 by the dashed vertical lines, whose positions are fixed by the sequence of highest energy losses as found for 200 K and 145 K. The intraconfigurational transition energies are in first order temperature independent. Any shifts of these energies due to temperature-dependent mixing or local-environment effects should increase with increasing  $J$  value. Such a behavior is found by incorporation of the free rare-earth ion into the solid, like for  $\text{SmSe}$  or  $\text{SmS}$ ,<sup>6</sup> but is not observed in  $\text{EuPd}_2\text{Si}_2$ . At 300 K the more intense interconfigurational excitations  $E_{L,\text{inter}}$  (indicated by tick marks) are slightly shifted to lower energy with respect to the dashed lines, implying  $E_x \approx 50 \text{ cm}^{-1}$  (70 K). At 200 K a further increase of  $E_x$  ( $E_x \approx 150 \text{ K}$ ) is indicated by the asymmetric broadening of the peaks at their low-energy side. The clearest evidence for a pronounced increase in  $E_x$  ( $E_x \approx 350 \text{ K}$ ) is found in the spectrum at 145 K, in which the  $E_{L,\text{intra}}$  and  $E_{L,\text{inter}}$  peaks are clearly split. At 77 K this splitting has disappeared, although the energy positions of the dominant

interconfigurational excitations  $E_{L,inter}$  (see tick marks) imply that  $E_x$  is still about the same as at 145 K. The spectrum at 5 K shows again rather narrow peaks near the positions of the dashed lines, implying that  $E_x$  is about of the order of the room-temperature value. The temperature dependence of  $E_x$  directly revealed in our Raman spectra is plotted in Fig. 3(a).

We will now consider the temperature dependence of  $T_f$ , characterizing the quantum-mechanical mixing of the two  $4f$  configurations (see bottom of Fig. 2). This information is mainly contained in the *spectral width* of the Raman peaks. Although the experimentally observed widths of the different  $J$  levels differ significantly at 300 K, their additional variations upon cooling below 300 K are very similar. Since we observe the joint mixing width of initial and final state in the scattering process, we ascribe the temperature-dependent common contribution to the width of all energy-loss peaks primarily to  $T_f$  of the initial state (ground state). The upper limit of  $T_f$  of the ground state is set by the narrowest energy-loss peak observable, i.e.,  $J=1$  at 300 and 5 K, and  $J=3$  at all other temperatures. These values inferred from the spectral features are presented in Fig. 3(b) as a function of temperature.

This independent determination of  $E_x$  and of the upper limit of  $T_f$  is consistent for the following reasons. At 300 K,  $T_f$  is of the order of  $E_x$  and therefore no splitting between the  $E_{L,inter}$  and  $E_{L,intra}$  excita-

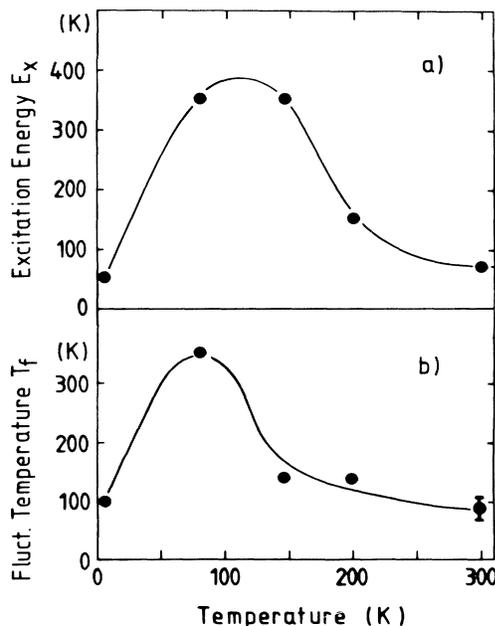


FIG. 3. Temperature dependence of (a) the interconfigurational excitation energy ( $E_x$ ) and (b) the upper limit of the fluctuation temperature  $T_f$  of  $\text{EuPd}_2\text{Si}_2$  as directly revealed in the Raman spectra of Fig. 1.

tions is detectable. At 200 K,  $T_f$  is slightly smaller than  $E_x$ , thus allowing for the observation of the asymmetric broadening of the peaks. Because of the much smaller  $T_f$  at 145 K compared to  $E_x$  the splitting between  $E_{L,intra}$  and  $E_{L,inter}$  excitations is most clearly seen. The disappearance of this splitting at 77 K is due to the dramatic increase of  $T_f$  to a value equal in magnitude to  $E_x$ , namely 350 K. At 5 K the upper limit of  $T_f$  is larger than  $E_x$  and consequently no splitting can be detected.

It is most encouraging that our data in Fig. 3 show good qualitative agreement with those obtained by Schmiester *et al.*,<sup>4</sup> on totally different experimental grounds. By use of the ionic ICF model, these authors have deduced the temperature dependence of  $E_x$  and  $T_f$  for  $\text{EuPd}_2\text{Si}_2$  from the Mössbauer isomer shift and the magnetic susceptibility. While the plateau of  $E_x$  near 100 K is found in both analyses, our maximum  $E_x \approx 350$  K is somewhat smaller than  $E_x \approx 500$  K deduced in Ref. 4. We note here that a consistent interpretation of our data is achieved only with  $E_x > 0$  at 300 K, contrary of Ref. 4. However, since  $k_B T \gg E_x$  this is not in conflict with the valence  $v = 2.2$  at 300 K.<sup>7</sup> In agreement with Ref. 4 the maximum of  $T_f$  is found near 80 K.

We have also performed Raman scattering measurements on mechanically polished samples of  $\text{EuPd}_2\text{Si}_2$ . It is known that the polishing may produce residual stresses up to about 10 kbar within the scattering volume.<sup>7</sup> This would actually allow us to check whether the present data are consistent with the temperature-pressure phase diagram.<sup>8</sup> The Raman spectrum of the polished sample at 300 K did not exhibit the detailed multiplet structure shown in Fig. 1, except for one prominent peak near  $330 \text{ cm}^{-1}$  (480 K). Because of its strong intensity it is attributed to the interconfigurational excitation  $E_x$  between the  $J=0$  initial state and the  $J=\frac{7}{2}$  final state, which is close in energy to the  $J=1$  level. Interestingly enough, this spectroscopically observed value of  $E_x$  is in good agreement with that deduced in Ref. 4 at 300 K for a pressure of 10 kbar.

In previous Raman studies on  $\text{Sm}_{1-x}\text{Y}_x\text{S}$ <sup>6</sup> no evidence of the  $J$ -multiplet levels was found for concentrations beyond configuration crossover ( $x > 0.15$ ). However, the situation in  $\text{Sm}_{1-x}\text{Y}_x\text{S}$  is more complicated because of the  $\text{Sm}^{3+}4f^5(^6H_J)$  configuration as compared to the single  $4f^7(^8S_{7/2})$  level of  $\text{Eu}^{2+}$ . The  $4f^5$  configuration shows a splitting of about  $900 \text{ cm}^{-1}$  between the  $J=\frac{5}{2}$  and  $J=\frac{7}{2}$  levels, and additionally both may also be further split by the crystalline electric field. Moreover, in a solid-solution system inhomogeneous broadening of the  $J$  levels may also play a role. On the other hand, in our Raman study of  $\text{EuPd}_2\text{Si}_2$  the use of different laser excitation energies  $\hbar\omega_i$  resulted in an overall resonantly enhanced scatter-

ing cross section for  $\hbar\omega_i \approx 2.4$  eV, most likely due to strong  $f$ - $d$  electric-dipole transitions.

In conclusion we would like to emphasize that electronic Raman scattering in  $\text{EuPd}_2\text{Si}_2$  has given the first direct spectroscopic evidence for the persistence of intraionic  $J$ -multiplet levels in an intermediate-valence state. Until now this could be inferred only indirectly from maxima in the nonlinear relationship of  $T_f(E_x)$ .<sup>3</sup> Furthermore, our Raman spectra have enabled us to evaluate directly the temperature dependence of  $E_x$  and of the upper limit of  $T_f$ . So far  $E_x$  and  $T_f$  have been obtained as adjustable parameters from susceptibility and Mössbauer data analysis by use of the ionic ICF model.<sup>3-5,9,10</sup> The dramatic valence change of  $\text{EuPd}_2\text{Si}_2$  near 150 K<sup>4,8-10</sup> has been shown to arise from the near degeneracy of the  $(\text{Eu}^{2+}) J = \frac{7}{2}$  and the  $(\text{Eu}^{3+}) J = 1$  levels and their interconfigurational mixing. We believe that the results reported in this paper provide direct experimental verification of the underlying assumptions of the ionic ICF model.

In recent neutron-scattering experiments on  $\text{EuPd}_2\text{Si}_2$ <sup>11</sup> the quasielastic linewidth has been determined, which agrees above 50 K with our temperature dependence of the upper limit of  $T_f$ .

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